

Control of Impurity Diffusion in Semiconductors by Intensive IR Excitations

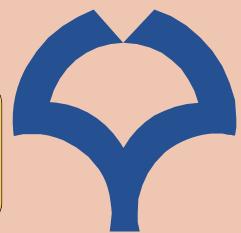


K. Shirai, K. Matsukawa[†], T. Moriwaki^{††}, and Y. Ikemoto^{††}

Nanoscience and Nanotechnology center, ISIR, Osaka University

[†] Renesas Technology Corp.

^{††} Sprint-8/JASRI



<p>1. motivation</p> <p>Idea of selective diffusion by excitation of impurity vibrations</p> <p>laser frequency ν_{ir} Resonance vibration frequency $\nu_n = \nu_p$</p> <p>excitation of the motion of a selective species only</p> <p>Laser ν_{ir} Diffusion process can be switched on and off</p> <p>Only the excited impurity migrates</p>	<p>2. purpose</p> <p>Selective impurity diffusion by IR excitation</p> <p>Promotion of diffusion of a specific impurity by using resonance excitation at the impurity mode.</p> <ul style="list-style-type: none"> • Problem no availability of suitable IR laser • Computer simulation Design of light source <p>First attempt of excitation of O by SPRing-8</p> <p>BL43IR</p>	<p>3. diffusion length</p> <p>Diffusion of Oxygen</p> <p>$D = D_0 \exp(-Q/kT)$</p> <p>$D [cm^2/s] = 0.194 \exp(-2.54[eV]/kT)$</p> <p>T. Y. Tan and U. Gösele, Appl. Phys. A37 1 (1985)</p> <table border="1"> <thead> <tr> <th>T [K]</th> <th>eV</th> <th>D [cm²/s]</th> <th>t [ns]</th> <th>l_0 [nm]</th> </tr> </thead> <tbody> <tr> <td>1500</td> <td>0.086</td> <td>3.0×10^{-11}</td> <td>10^1</td> <td>0.3</td> </tr> <tr> <td>1600</td> <td>0.137</td> <td>1.9×10^{-10}</td> <td>10^1</td> <td>0.1</td> </tr> <tr> <td>2000</td> <td>0.172</td> <td>7.6×10^{-10}</td> <td>10^2</td> <td>2.7</td> </tr> <tr> <td>2500</td> <td>0.215</td> <td>1.4×10^{-9}</td> <td>10^2</td> <td>0.27</td> </tr> <tr> <td>3000</td> <td>0.258</td> <td>1.0×10^{-9}</td> <td>10^2</td> <td>0.3</td> </tr> </tbody> </table>	T [K]	eV	D [cm ² /s]	t [ns]	l_0 [nm]	1500	0.086	3.0×10^{-11}	10^1	0.3	1600	0.137	1.9×10^{-10}	10^1	0.1	2000	0.172	7.6×10^{-10}	10^2	2.7	2500	0.215	1.4×10^{-9}	10^2	0.27	3000	0.258	1.0×10^{-9}	10^2	0.3
T [K]	eV	D [cm ² /s]	t [ns]	l_0 [nm]																												
1500	0.086	3.0×10^{-11}	10^1	0.3																												
1600	0.137	1.9×10^{-10}	10^1	0.1																												
2000	0.172	7.6×10^{-10}	10^2	2.7																												
2500	0.215	1.4×10^{-9}	10^2	0.27																												
3000	0.258	1.0×10^{-9}	10^2	0.3																												
<p>4. power balance</p> <p>Power Dependence</p> <p>B mode</p> <p>$P_{atom} = \frac{\Delta E}{\tau}$</p> <p>input power deviation from therm. eq. relaxation time $\tau \sim 1 \text{ ps}$</p>	<p>5. power consideration</p> <p>Power consideration</p> <p>$E_{phonon} < E_{pulse} < E_{decay}$</p>	<p>6. power required</p> <p>Intensity of laser power</p> <p>For an atom $P_{atom} = \frac{\Delta E}{\tau}$ deviation of atom energy from thermal equilibrium 0.22 eV phonon relaxation time 10 ps</p> <p>$P_{atom} = 1 \times 10^{10} [\text{W}/\text{atom}]$</p> <p>impurity concentration $n = 1 \times 10^{18} / \text{cm}^3$ $P_{abs} = n \times P_{atom} = 1 \times 10^9 [\text{W}/\text{cm}^3]$</p> <p>absorption coefficient $\alpha = 1 \times 10^4 [\text{cm}^{-1}]$ $I_{in} = P_{abs} / \alpha = 1 \times 10^5 [\text{W}/\text{cm}^2]$</p> <p>$P_{pulse} = 1 \times 10^5 \text{ W/cm}^2$</p>																														
<p>7. estimate</p> <p>BL43IR</p> <p>$P_{atom} = 2.6 \times 10^{-12} \text{ W/atom}\cdot\text{pulse}$</p> <p>$\langle J \rangle = 0.15 \mu\text{W}/\text{cm}^2$ at 1000 cm^{-1}</p> <p>beam size $150 \times 100 \mu\text{m}$</p> <p>$< J > = 0.1 \text{ W}/\text{cm}^2$ for width 100 cm^2</p> <p>$J_{pulse} = \frac{15}{100} \cdot \frac{\tau_{ref}}{\tau_{pulse}} \times < J > = 256 \text{ W}/\text{cm}^2\cdot\text{pulse}$</p>	<p>8. apparatus</p> <p>BL43IR</p> <p>SIMS depth profile for B</p> <p>BL43IR-SIMS depth profile</p>	<p>9. beam data</p> <p>Beam data</p> <p>D mode</p> <p>$I_{diffusion} = I_{irr} \times \frac{\tau_{pulse}}{\tau_{intervall}}$</p> <p>$12(\text{hrs}) \times \frac{40(\text{ps})}{684.3(\text{ns})} = 2.5(\text{sec})$</p>																														
<p>10. sample</p> <p>Samples</p> <p>IR irradiation 12 hrs irradiation</p> <p>O: 1100 cm^{-1} B: 520 cm^{-1}</p> <p>Filtering</p> <table border="1"> <thead> <tr> <th></th> <th>O</th> <th>B</th> </tr> </thead> <tbody> <tr> <td>BP2432-1333</td> <td>x</td> <td>x</td> </tr> <tr> <td>LP1450</td> <td>o</td> <td>o</td> </tr> </tbody> </table>		O	B	BP2432-1333	x	x	LP1450	o	o	<p>11. result</p> <p>Detection of change in diffusion by SIMS depth profile</p> <p>SIMS O profile</p> <p>BL43IR</p> <p>LP1450</p> <p>BP2432-1333</p> <p>SIMS depth profile for B</p> <p>BL43IR</p> <p>LP1450</p> <p>BP2432-1333</p>	<p>12. Summary</p> <p>Summary</p> <ol style="list-style-type: none"> First attempt of IR excitation of impurity diffusion has been failed. The most significant error comes from the estimate of the input power at the sample. The present experience of power estimation could bring about success in the next stage of experiment. 																					
	O	B																														
BP2432-1333	x	x																														
LP1450	o	o																														